

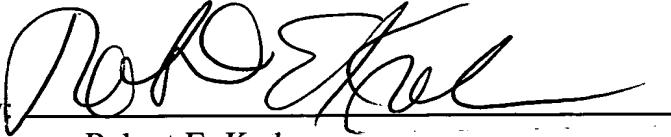
REMARKS

The claims of the subject application have been amended to avoid multiple dependency. Favorable consideration of the subject application is respectfully requested.

Attached hereto is a marked-up version of the changes made to the claims by the current amendment. The attached page is captioned "Version with markings to show changes made."

Respectfully submitted,

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VERSION WITH MARKINGS TO SHOW CHANGES MADE

In the claims:

Claim 19, 20, and 21 have been amended as follows:

19. (Amended) A process according to ~~one of claims 12 and 15~~, wherein stage a) comprises:

- delimiting the active zone according to a field oxidation (LOCOS) or shallow trench isolation technique, and
- doping the active area so as to give it the first conductivity type.

20. (Amended) A process according to ~~one of claims 12 and 15~~, wherein the formation of the conductive layer (180) is preceded by the formation of lateral spacers (181) on the gates.

21. (Amended) A process according to ~~one of claims 12 and 15~~, wherein the conductive layer (180) is a layer of silicide.

Claims 22-24 have been added.